### **Quantum Imaging: New Methods and Applications**

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## **Research in Quantum Imaging**

Can images be formed with higher resolution or better sensitivity through use of quantum states of light?

Can we "beat" the Rayleigh criterion?

What are the implications of "interaction free" and "ghost" imaging

Quantum states of light: For instance, squeezed light or entangled beams of light.

Ghost and Interaction-Free Imaging

**Stealth Imaging** 

### Quantum Imaging by Interaction-Free Measurement



A. Elitzur and L. Vaidman, Foundations of Physics, 23 987 (1993). Kwiat, Weinfurter, Herzog, Zeilinger, and Kasevich, Phys. Rev. Lett. 74 4763 1995 White, Mitchell, Nairz, and Kwiat, Phys. Rev. A58, 605 (1998).

# Ghost (Coincidence) Imaging



# **Classical Coincidence Imaging**

We have performed coincidence imaging with a demonstrably classical source.





Bennink, Bentley, and Boyd, Phys. Rev. Lett. 89 113601 (2002).

### **Ghost Diffraction with a Classically Correlated Source**



Bennink, Bentley, Boyd, and Howell, PRL 92 033601 (2004)

## Further Development

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# Entangled Imaging and Wave-Particle Duality: From the Microscopic to the Macroscopic Realm

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We formulate a theory for entangled imaging, which includes also the case of a large number of photons in the two entangled beams. We show that the results for imaging and for the wave-particle duality features, which have been demonstrated in the microscopic case, persist in the macroscopic domain. We show that the quantum character of the imaging phenomena is guaranteed by the simultaneous spatial entanglement in the near and in the far field.

DOI: 10.1103/PhysRevLett.90.133603

PACS numbers: 42.50.Dv, 03.65.Ud

#### **Near- and Far-Field Imaging Using Quantum Entanglement**



Good imaging observed in both the near and far fields!

Bennink, Bentley, Boyd, and Howell, Phys. Rev. Lett., 92, 033601, 2004.

### **Near- and Far-Field Imaging With a Classical Source**



• Good imaging can be obtained only in near field or far field.

• Detailed analysis shows that in the quantum case the spacebandwidth exceeded the classical limit by a factor of ten.

### Is Entanglement Really Needed for Ghost Imaging with an Arbitrary Object Location?

Gatti et al. (PRA and PRL, 2004) argue that thermal sources can mimic the quantum correlations produced by parametric down conversion. (Related to Brown-Twiss effect.)

Experimental confirmation of ghost imaging with thermal sources presented by Como and UMBC groups

But the contrast of the images formed in this manner is limited to 1/2 or 1/N (depending on the circumstances) where N is the total number of pixels in the image.

## **Remote (Ghost) Spectroscopy**



Can this idea be implemented with thermal light? Scarcelli, Valencia, Compers, and Shih, APL 83 5560 2003.See also the related work of Bellini et al., Phys. Rev. Lett. 90 043602 (2003). Progress in Quantum Lithography

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### Quantum Lithography

- Entangled photons can be used to form an interference pattern with detail finer than the Rayleigh limit
- Process "in reverse" performs sub-Rayleigh microscopy, etc.
- Resolution  $\approx \lambda / 2N$ , where N = number of entangled photons



Boto et al., Phys. Rev. Lett. 85, 2733, 2000. ("al." includes Jon Dowling)

## **Quantum Lithography: Easier Said Than Done**

• Need an *N*-photon recording material

For proof-of-principle studies, can use N-th-harmonic generator, correlation circuitry, N-photon photodetector.
For actual implementation, use ????
Maybe best bet is UV lithographic material excited in the visible or a broad bandgap material such as

PMMA excited by multiphoton

absorption.

3PA in PMMAbreaks chemicalbond, modifyingoptical properties.Problem: selfhealing

 Need an intense source of individual biphotons (Inconsistency?) Maybe a high-gain OPA provides the best tradeoff between high intensity and required quantum statistics

#### Use of High-Gain Parametric Amplifier

Is two-photon interference pattern preserved?



two-photon recording medium

• Transfer equations of OPA

where 
$$\hat{a}_1 = U\hat{a}_0 + V\hat{b}_0^{\dagger}, \quad \hat{b}_1 = U\hat{b}_0 + V\hat{a}_0^{\dagger}$$
  
 $U = \cosh G \qquad V = -i\exp(i\varphi)\sinh G$ 

· Field at recording medium

$$\hat{a}_3 = \frac{1}{\sqrt{2}} \left[ (-e^{i\chi} + i)(U\hat{a}_0 + V\hat{b}_0^{\dagger}) + (ie^{i\chi} - 1)(U\hat{b}_0 + V\hat{a}_0^{\dagger}) \right]$$

Two-photon absorption probablility



#### **QUANTUM LITHOGRAPHY RESEARCH**

#### **Experimental Layout**





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### Classically Simulated (Non-Quantum) Quantum Lithography

Concept: average M shots with the phase of shot k given by  $2\pi k/M$ 





S. J. Bentley and R.W. Boyd, Optics Express, 12, 5735 (2004).

One-photon absorber (N=1, M=1)



Two-photon absorber (N=2, M=1)



Two-photon absorber two exposures (N=2, M=2)



### **Spatial Resolution of Various Systems**

• Linear optical medium

 $\mathbf{E} = \mathbf{1} + \cos \mathbf{k} \mathbf{x}$ 



- Two-photon absorbing medium, classical light  $E = (1 + \cos kx)^2 = 1 + 2 \cos kx + \cos^2 kx$   $= 3/2 + 2 \cos kx + (1/2) \cos 2kx$
- Two-photon absorbing medium, entangled photons E = 1 + cos 2kx

where  $k = 2(/c) \sin ($ 

### Demonstration of Fringes Written into PMMA



 $\theta$  = 70 degrees write wavelength = 800 nm pulse energy = 130 µJ per beam pulse duration = 120 fs period =  $\lambda$  / (2 sin  $\theta$ ) = 425 nm

PMMA on glass substrate develop for 10 sec in MBIK rinse 30 sec in deionized water





AFM



PMMA is a standard lithographic material

### Demonstration of Sub-Rayleigh Fringes (Period = $\lambda/4$ )



N-photon absorber



 $\theta$  = 70 degrees two pulses with 180 deg phase shift write wavelength = 800 nm pulse energy = 90 µJ per beam fundamental period =  $\lambda$  / (2 sin  $\theta$ ) = 425 nm period of written grating = 212 nm

PMMA on glass substrate develop for 10 sec in MBIK rinse 30 sec in deionized water



### **Further Enhancement?**

PMMA is at least a 3PA @ 800 nm, so further enhancement should be possible.

• Illuminate with two pulses with a  $2\pi/3$  phase-shift.





#### 1/6 the recording wavelength!



SPIE: Aug. 14th, 2006

## **Significance of PMMA Grating Results**

- Provides an actual demonstration of sub-Rayleigh resolution by the phase-shifted grating method
- Demonstrates an N-photon absorber with adequate resolution to be of use in true quantum lithography

### **Summary**

Quantum lithography has a good chance of becoming a reality.

The quantum vs. classical nature of ghost imaging is more subtle than most of us had appreciated.

Many of our cherished "quantum effects" can be mimicked classically.

There is still work to be done in the context of quantum imaging to delineate the quantum/classical frontier.

## **Special Thanks to My Students and Research Associates**



#### Thank you for your attention!



Physics is all about asking the right questions Just ask

Evelyn Hu

Watt Webb (or James Watt)

Michael Ware

Wen I Wang

Kam Wai Chan

Not to mention

Lene Hau